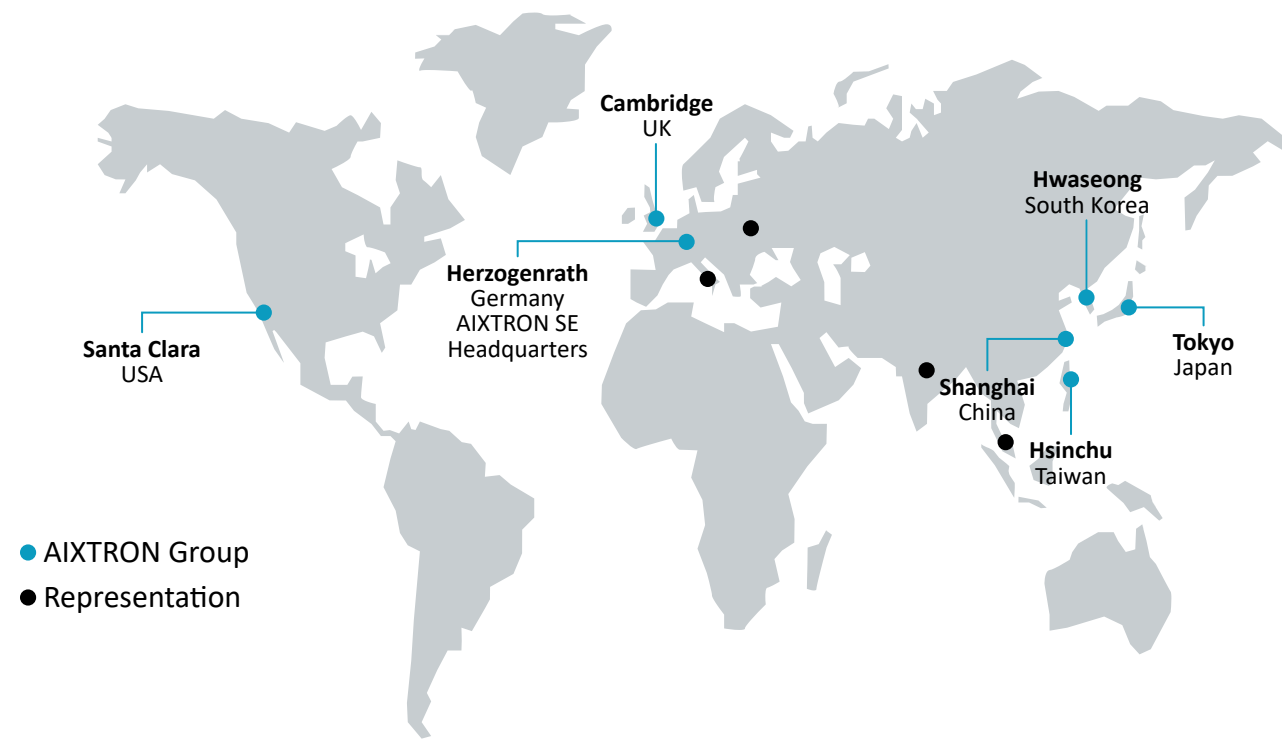




Cassette-to-Cassette Wafer Handling

- Fully automated loading of wafers
- Compatible with current and future wafer sizes
75 mm | 100 mm | 150 mm | 200 mm | optional SMIF port
- Vacuum cassette elevators for 2 x 25 wafer cassettes
- Clean environment for lowest defect levels
- Significant reduction of labor cost – both on operator and expert level

Global Presence



- AIXTRON Group
- Representation

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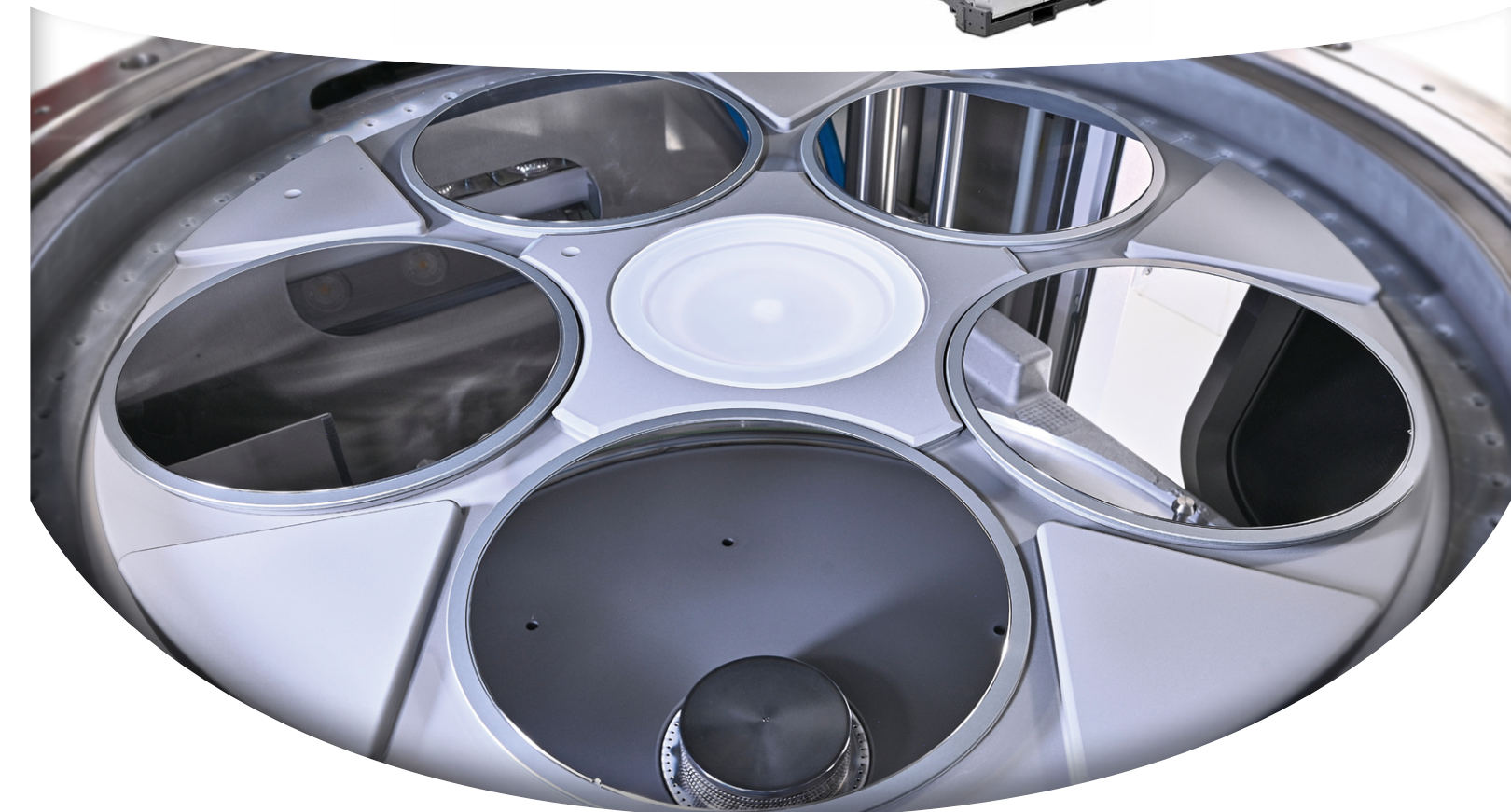
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G10-AsP

The Enabling MOCVD Solution

Fully Automated MOCVD for High Volume Production of GaAs/InP Materials

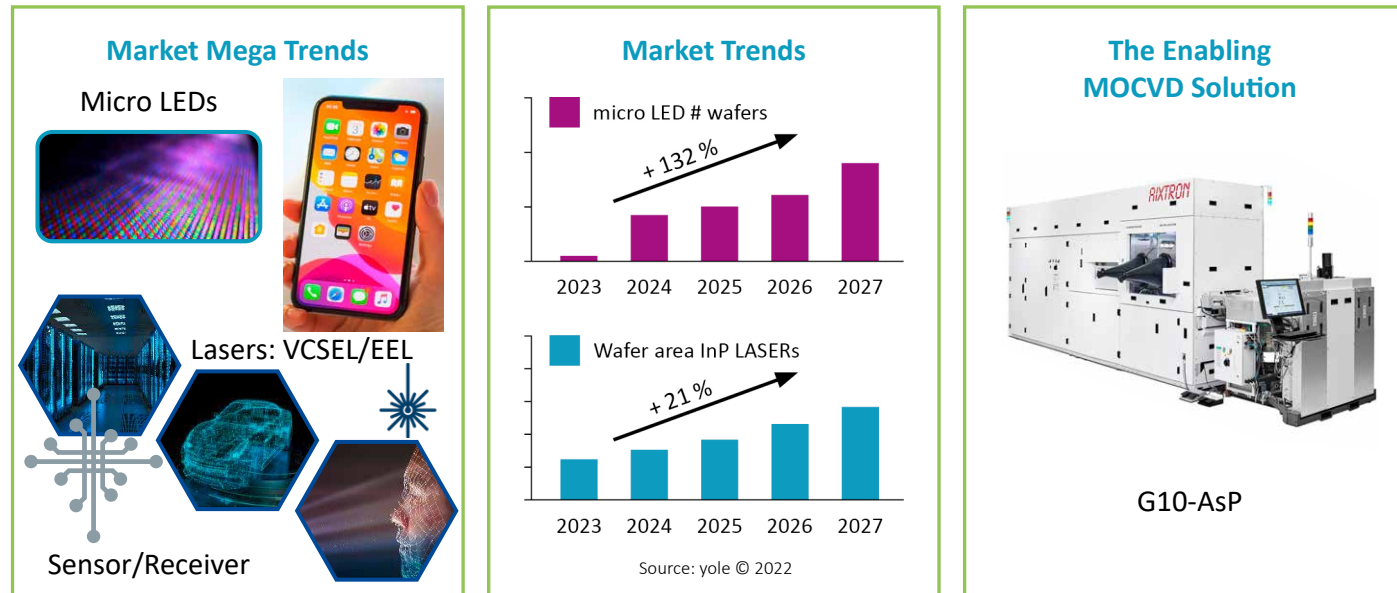


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Fully Automated MOCVD for High Volume Production of GaAs/InP Materials

Market Opportunity



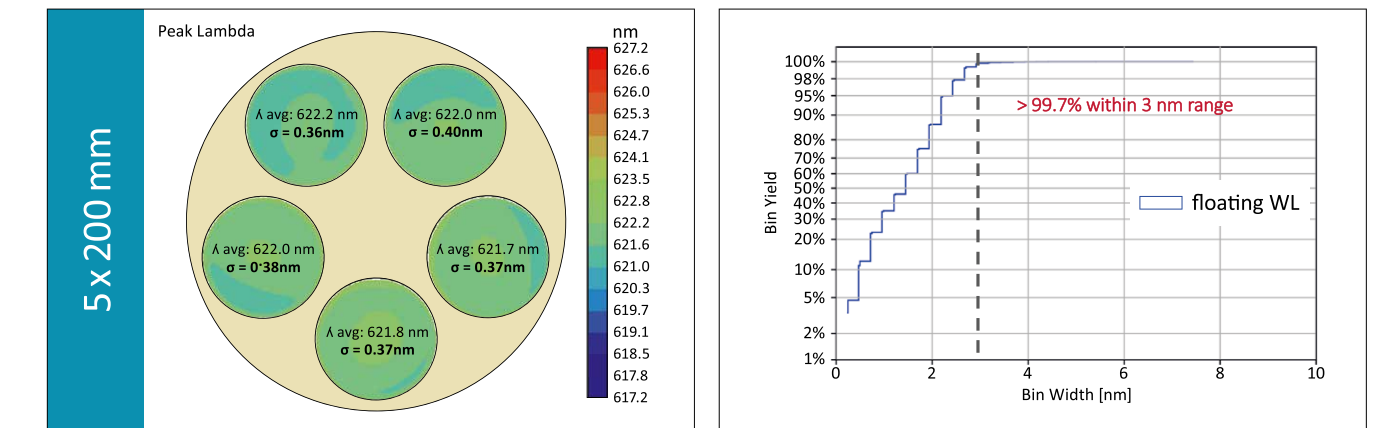
G10-AsP Planetary Reactor®



Addressing the tightened requirements of future markets

Best in class single wafer performance – throughout production campaign

Wavelength uniformity for Micro LEDs



PL Plot – Fully Loaded microLED Run (5 wafers)

Bin Yield (%) for all wafer area (21 x 200 mm wafers)

G10-AsP

- Future proof - Compatible with current and future wafer sizes 75 mm | 100 mm | 150 mm | 200 mm | optional SMIF port
- Highest uniformity and repeatability – throughout production campaigns
- Best particle performance in the market at lowest operational cost per good wafer



8 x 150 mm



5 x 200 mm

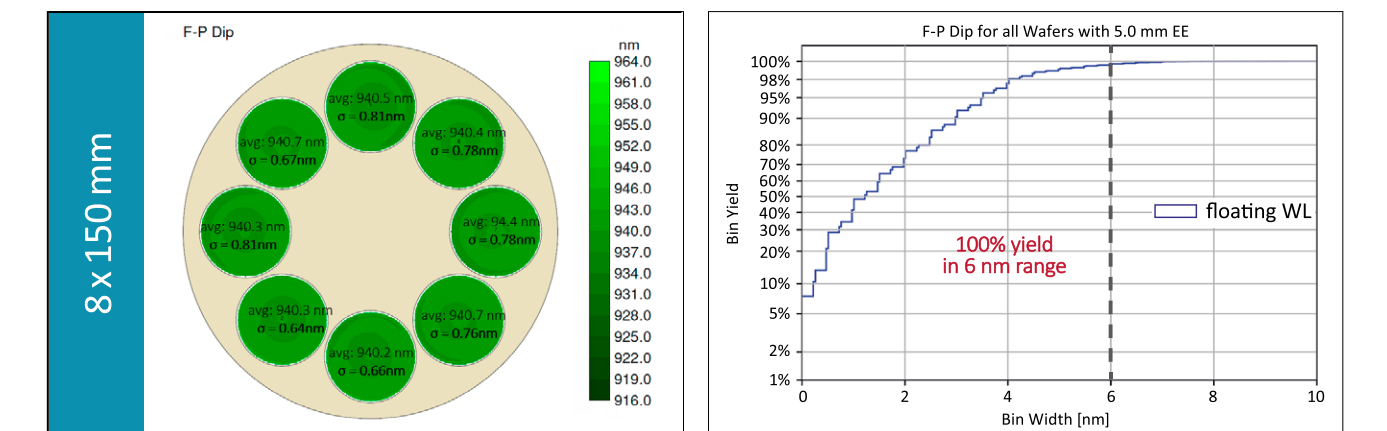
Your benefits

- Reduced labor cost, eliminate night shift
- Up to 10X lower particles, down to 0.1/cm²
- Unsurpassed reproducibility
- Exceptionally long campaigns
- Best in class yields
- Highest quality epitaxial layers
- Best Cost of Ownership
- Highest throughput of its class

Our solutions

- Fully automated processes with Cassette-to-Cassette handling
- Automated chamber etch back
- Planetary technology with single wafer performance
- Wafer-level control of uniformity and temperature by numerous chamber design innovations
- Largest capacity batch reactor platform for maximized Fab output
- Unmatched chemical efficiency by novel reactor design innovations

F-P Dip uniformity for VCSEL



F-P Dip – Fully Loaded VCSEL Run (8 wafers)

F-P Dip Yield for 10 fully loaded runs VCSEL Campaign (80 wafers)